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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
09/914,928	09/06/2001	Loick Verger	034299-346 5963		
7590 11/15/2005			EXAMINER		
Thelen Reid & Priest LLP P.O. Box 640640			SUNG, CHRISTINE		
San Jose, CA 95164-0640			ART UNIT	PAPER NUMBER	
			2884		

DATE MAILED: 11/15/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary		Applicatio	n No.	Applicant(s)				
		09/914,92	8	VERGER ET AL.	(m)			
		Examiner		Art Unit				
		Christine S	ung	2884				
Period fo	 The MAILING DATE of this communication Reply 	on appears on the	cover sheet with the c	orrespondence addre	ss -			
THE - External after - If the - If NO - Failu Any	ORTENED STATUTORY PERIOD FOR I MAILING DATE OF THIS COMMUNICAT nsions of time may be available under the provisions of 37 SIX (6) MONTHS from the mailing date of this communicar period for reply specified above is less than thirty (30) day to period for reply is specified above, the maximum statutory re to reply within the set or extended period for reply will, by reply received by the Office later than three months after the patent term adjustment. See 37 CFR 1.704(b).	FION. CFR 1.136(a). In no eve tion. s, a reply within the statu period will apply and will y statute, cause the appli	nt, however, may a reply be tin tory minimum of thirty (30) day expire SIX (6) MONTHS from cation to become ABANDONE	nely filed s will be considered timely. the mailing date of this comm D (35 U.S.C. § 133).	unication.			
Status								
1)⊠	Responsive to communication(s) filed or	n 19 August 2005.						
•=	This action is FINAL . 2b)⊠ This action is non-final.							
3)	, —							
Dispositi	ion of Claims							
5)□ 6)⊠ 7)□	4) ☐ Claim(s) 1-13 is/are pending in the application. 4a) Of the above claim(s) is/are withdrawn from consideration. 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-13 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/or election requirement.							
Applicat	ion Papers							
10)⊠	The specification is objected to by the Ex The drawing(s) filed on <u>06 September 20</u> Applicant may not request that any objection Replacement drawing sheet(s) including the The oath or declaration is objected to by	001 is/are: a)⊠ a to the drawing(s) b correction is require	e held in abeyance. See ed if the drawing(s) is ob	e 37 CFR 1.85(a). jected to. See 37 CFR	1.121(d).			
Priority (ınder 35 U.S.C. § 119							
 12) ☒ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) ☒ All b) ☐ Some * c) ☐ None of: 1. ☐ Certified copies of the priority documents have been received. 2. ☐ Certified copies of the priority documents have been received in Application No 3. ☒ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 								
2) Notice 3) Infor	et(s) ce of References Cited (PTO-892) ce of Draftsperson's Patent Drawing Review (PTO-9) mation Disclosure Statement(s) (PTO-1449 or PTO er No(s)/Mail Date		4) Interview Summary Paper No(s)/Mail D 5) Notice of Informal F 6) Other:		52)			

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Response to Amendment

1. The amendment filed on August 19, 2005 has been entered.

Claim Rejections - 35 USC § 103

- 2. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 3. Claims 1-4, 7-9, 11-13 are rejected under 35 U.S.C. 103(a) as being unpatentable over Jeromin (US Patent 5,381,014 A) in view of Gale (US Patent 4,585,513A).

Regarding claim 1, Jeromin discloses and x-ray imagery device (figure 1) comprising at least one detection matrix made of a semiconducting material (elements 14,15 and 19), said detection matrix comprising:

Pixels (elements 17) to convert incident x-photons into electric charges (Column 3, line 1);

An electric charges reading panel (element 15) including a plurality of electronic devices (element 19), each electronic device be integrated by pixel (elements 17 and 19);

A detection layer (element 14) made of a continuous layer of semiconducting material deposited in vapor phase (column 3, lines 27-30) on the electric charges reading panel (see figure 1). Jeromin does not specify that the electric charges reading panel is made of monocrystalline silicon. However, Gale discloses a conventional single crystalline silicon substrate or electric charges reading panel (column 2, lines 23-38). One of ordinary skill in the art would be motivated to use the substrate or electric charges reading panel as disclosed by Gale with the

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invention as disclosed by Jeromin as single crystalline silicon has greater detection efficiency than selenium as disclosed by Jeromin. Further, one of ordinary skill in the art would be motivated to use the detection material as disclosed by Gale with the invention as disclosed by Jeromin as silicon is a well known and well studied imager material, thus use of such material would decrease the difficulty of mass manufacturing.

Regarding claim 2, Jeromin discloses a process for making an x-ray image device (figure 1) comprising at least one detection matrix made of a semiconducting material (elements 14, 15 and 19), said detection matrix comprising pixels (element 17) to convert incident x-photons into electric charges (column 3, line 1) and an electric charges reading panel (element 15) including a plurality of electronic devices (element 19), each electronic device being integrated by pixel (elements 17 and 19), wherein each detection matrix is obtained by vapor phase deposition of a semiconductor on the electric charges reading panel (column 3, lines 27-30) on the electric reading panel (see figure 1). Jeromin does not specify that the electric charges reading panel is made of monocrystalline silicon. However, Gale discloses a conventional single crystalline silicon substrate or electric charges reading panel (column 2, lines 23-38). One of ordinary skill in the art would be motivated to use the substrate or electric charges reading panel as disclosed by Gale with the invention as disclosed by Jeromin as single crystalline silicon has greater detection efficiency than selenium as disclosed by Jeromin. Further, one of ordinary skill in the art would be motivated to use the detection material as disclosed by Gale with the invention as disclosed by Jeromin as silicon is a well known and well studied imager material, thus use of such material would decrease the difficulty of mass manufacturing.

Regarding claim 3, although Jeromin in view of Gale does not explicitly state that the specific temperature of the deposition process of the semiconducting material be at a temperature that does not damage the electronic devices, it would have been obvious to one having ordinary skill in the art to have chosen a semiconducting material whose vaporization temperature would not exceed the highest tolerable temperature of the electronic devices, so as to not render the device useless.

Regarding claim 4, Jeromin discloses that the semiconducting material is made of mercuric iodide (Column 3, lines 47-48).

Regarding claim 7, Jeromin discloses that the detection layer (element 14) is deposited directly on the electronic devices (element 19) of the electric charges reading panel (element 15) in each pixel.

Regarding claim 8, Jeromin discloses that the detection layer is made of semiconducting material (see abovementioned paragraphs), but does not specify crystalline silicon. However, although Jeromin does not specify that crystalline silicon is used, he does disclose that crystalline is a well known semiconductor (column 5, lines 49-53), and further teaches that the specific type of radiation detecting material selected will depend upon the desired charge generation efficiency. One of ordinary skill in the art would be motivated to use crystalline silicon as the detection layer because it has excellent detection efficiency, which would increase the accuracy of the detected data.

Regarding claim 9, Jeromin discloses that element 19, is a transistor-capacitor element, which inherently contains an amplifier, a preamplifier and filter. Further, Jeromin discloses that the detector has an image processor (Column 7, lines 23-39).

Regarding claim 11, Jeromin discloses a method for making an x-ray image device (figure 1) comprising at least one detection matrix made of a semiconducting material (elements 14, 15 and 19), said detection matrix comprising pixels (element 17) to convert incident x-photons into electric charges (column 3, line 1) and an electric charges reading panel (element 15) including a plurality of electronic devices (element 19), each electronic device being integrated by pixel (elements 17 and 19), said method comprising:

Forming the electronic devices (element 19) on a substrate (element 13) to produce the electric charges reading panel (element 15) of each detection matrix; and

vapor phase depositing a semiconductor on the electric charges reading panel (column 3, lines 27-30) on the electric reading panel (see figure 1) so as to form a detection layer (element 14) made of a continuous layer of the semiconducting material.

Jeromin does not specify that the electric charges reading panel is made of monocrystalline silicon. However, Gale discloses a conventional single crystalline silicon substrate or electric charges reading panel (column 2, lines 23-38). One of ordinary skill in the art would be motivated to use the substrate or electric charges reading panel as disclosed by Gale with the invention as disclosed by Jeromin as single crystalline silicon has greater detection efficiency than selenium as disclosed by Jeromin. Further, one of ordinary skill in the art would be motivated to use the detection material as disclosed by Gale with the invention as disclosed by Jeromin as silicon is a well known and well studied imager material, thus use of such material would decrease the difficulty of mass manufacturing.

Regarding claim 12, although Jeromin in view of Gale does not explicitly state that the specific temperature of the deposition process of the semiconducting material be at a temperature

that does not damage the electronic devices, it would have been obvious to one having ordinary skill in the art to have chosen a semiconducting material whose vaporization temperature would not exceed the highest tolerable temperature of the electronic devices, so as to not render the device useless.

Regarding claim 13, Jeromin discloses assembling more than one detection matrix to form a large area digital detector (see figure 4).

4. Claims 5-6 are rejected under 35 U.S.C. 103(a) as being unpatentable over Jeromin (US Patent 5,381,014 A) in view of Gale (US Patent 4,585,513A) further in view of the admitted prior art.

Regarding claims 5-6, Jeromin in view of Gale does not specify that the electronic devices are made using a process technology having feature device sizes of 0.1 micron or 1.25 microns. However, on page 7, lines 26-30 of the specification, applicant acknowledges that the feature sizes are conventional. One of ordinary skill in the art would be motivated to use the conventional feature device sizes in order to reduce costs and use conventional semiconductor device processing methods instead of developing non-conventional methods which are costlier.

5. Claim 10 is rejected under 35 U.S.C. 103(a) as being unpatentable over Jeromin (US Patent 5,381,014 A) in view of Gale (US Patent 4,585,513A) further in view of Mori et al (US Patent 4,591,984 A).

Regarding claim 10, Jeromin in view of Gale discloses the limitation set forth in claim 9, but does not specify the conventional processing circuit with a reading circuit and integration circuit and a counting circuit. Conventional processing techniques use such circuits in order to properly process the collected data, as demonstrated by Mori (see Figure 3, and column 2, line

59-column 3, line 3). On of ordinary skill in the art would be motivated to use the claimed circuits in order to properly process the detected image signals and to reduce errors.

Response to Arguments

- Applicant's arguments filed August 19, 2005 have been fully considered but they are not 6. persuasive.
- Applicant's arguments with respect to claims 1-13 have been considered but are moot in 7. view of the new ground(s) of rejection.
- Applicant requested an interview via the last response dated August 19, 2005. However, 8. Applicant was contacted via voicemail on October 31, 2005, but no reply was received. In order to reply in a timely fashion, the examiner has responded without having an interview. Should the applicant like to discuss any issues regarding the application, applicant is free to contact the examiner at the below listed telephone number.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Christine Sung whose telephone number is 571-272-2448. The examiner can normally be reached on Monday- Friday 7-3 pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David Porta can be reached on 571-272-2444. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Christine Sung

Examiner

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CS

PHIMARY EXAMINER